•	Application No.	Applicant(s)
	10/671,666	TANAKA ET AL.
Notice of Allowability	Examiner	Art Unit
	Kripa Sagar	1756
The MAILING DATE of this communication and claims being allowable, PROSECUTION ON THE MERIT in the mailed in the communication and communication are rewrith (or previously mailed), a Notice of Allowance (PTOL NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1	S IS (OR REMAINS) CLOSED in 85) or other appropriate commu NT RIGHTS. This application is s	this application. If not included inication will be mailed in due course. THIS
 This communication is responsive to <u>9/29/03</u>. The allowed claim(s) is/are <u>16-21</u>. The drawings filed on <u>29 September 2003</u> are accepted. Acknowledgment is made of a claim for foreign priority 		(f).
a) ⊠ All b) □ Some* c) □ None of the:		
1. Certified copies of the priority documents		N 00/040 404
2. Certified copies of the priority documents		•
3. Copies of the certified copies of the priorit		in this national stage application from the
International Bureau (PCT Rule 17.2(a	1)).	
* Certified copies not received: 5. Acknowledgment is made of a claim for domestic prior	rity under 35 H.S.C. & 119(e) (to :	a provisional application)
(a) ☐ The translation of the foreign language provisio		
6. Acknowledgment is made of a claim for domestic prior		
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DETAILED ACTION

Response to Amendment

- The preliminary amendment is acknowledged. Claims 1-15 are cancelled.
 Claims 16-21 are newly added; no new matter has been introduced by the amendment.
 Claims 16-21 are under consideration.
- 2. The preliminary amendment to the first line of the specification cross-referencing the parent application is acknowledged. It should include the phrase "now US Pat. 6,653,052".

EXAMINER'S AMENDMENT

3. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with attorney John Mattingly on 1/23/04.

The application has been amended as follows:

In the specification:

In the amendment to the first page of the specification: delete period (.) at end of line and add phrase ", now US Pat.6,653,052."

In the claims:

Claim 16; line 10: replace term "with" with "as".

Claim 20; line 12: replace term "with" with "as".

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Allowable Subject Matter

- 4. Claims 16-21 are allowed.
- 5. The following is an examiner's statement of reasons for allowance:

The independent claims recite a method of manufacturing an electron / semiconductor device with a mask that comprises a plurality of apertures formed in a resist light shielding area. Other elements include first and second phase shift patterns that are same in shape but mutually phase-inverted; and multiple exposures with the first and second patterns.

Applicant cited reference JP-05-298307 to Matsuo et al. teaches forming a light shielding layer with a photoresist; and comprising patterned openings (i.e. a darkfield mask). It does not teach phase shifting patterns.

Applicant cited reference, US Pat. 5348826 to Dao et al. teaches phase shift masks with first and second phase shift patterns that are mutually inverted in phase. The mask is a brightfield mask.

The combination of the references would not be obvious to one of ordinary skill in the art.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Kripa Sagar whose telephone number is 571-272-1392. The examiner can normally be reached on M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-

0661.

MH/ks

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